

Preliminary Agenda - Si/SiGe Epi user meeting						
Tuesday 21.10.2025 - Afternoon Session						Session Chair
12:30	Arrival					
13:00				Welcome and Introduction	0:00	Matthias Künle
13:00				Welcome and Introduction of participants	0:30	
13:30				Applications for Si-Epi 1	0:00	Olaf Fiedler
13:30	Malte	Czernohorsky	Fraunhofer IPMS	SiGe and Si epi processes on a 300mm batch furnace	0:25	
13:55	Wei-Chen	Wen	IHP - Leibniz Institute for High Performance Microelectronics	Tailoring SiGe Nanodot and Superlattice Structures for Co-Integration on a Single Wafer	0:25	
14:20				Epi Hardware 1	0:20	Marion Driesen
14:45	Anna	Vogel	Texas Instruments	AMAT Centura Inject Baffle Modification	0:25	
15:10	Steve	Burch	Helios Technical Services	Why the Semi industry leverages aftermarket companies instead of OEM for legacy equipment	0:25	
15:35	Maximilian	Rudloff	Robert Bosch Reutlingen	Potential risk of Chlorosilan residuals in the ductwork of Si-Epi tools	0:25	
16:00	Coffee break & networking				0:20	
16:20				Epi Process	0:20	Malte Czernohorsky
16:40	Christophe	Pomarede	ASM Germany	Tentative title only: High temperature Epi Si performance	0:25	
17:05	Marion/Charlotte	Drießen/Weiss	Fraunhofer ISE	Si and SiGe Epi for Photovoltaics	0:25	
17:30	Olaf	Fiedler	Infineon Dresden	Growth rate Stabilisation @ ATM EPI with concentration control of TCS	0:25	
17:55				Wrap up and end of day 1	4:50	Olaf Fiedler
19:00	All	Evening Event @ Freiburger Schankhaus near Frauenkirche				
Wednesday 22.10.2025 - Morning Session						
8:30	Arrival Day 2					
8:45				Welcome Day 2	0:15	
9:00				Applications for Si-Epi 2		Olaf Fiedler
9:00	Yuji	Yamamoto	IHP - Leibniz Institute for High Performance Microelectronics	Si Atomic Layer Epitaxy in Ge for Electro-Adsorption Modulator Integration	0:25	
9:25	Rick	Schwerdtfeger	NexWafe GmbH	New Results of Large Area APCVD for Silicon-based Photovoltaics	0:25	
9:50				Epi Hardware 2	0:15	Matthias Künle
10:05	Annekathrin	Zeun	Globalfoundries	EPI AMAT BASE PLATE cleaning/aging effect	0:25	
10:30	Matthias	Zieger	Infineon Regensburg	TBA	0:25	
10:55	Patrick	Mülverstedt	Robert Bosch Dresden	Uptime improvement - focus hardware Bosch DrP EPI 300	0:25	
11:20	Coffee break & networking				0:20	
11:40				Epi Process, Simulation and Metrology		Marion Driesen
11:40	Andreas	Zienert	Fraunhofer ENAS	Simulation of Si Epitaxy in Single Wafer Reactors	0:25	
12:05	Andreas	Nollau	Semilab Germany GmbH	Advanced epi metrology: crystal, thickness, doping	0:25	
12:30	Franz	Kammel	Robert Bosch Dresden	LIT focus spots after 20 µm EPI	0:25	
12:55				Closing remarks and end of day 2	0:00	Olaf Fiedler